

Appl. No. 10/712,876
Amtd. Dated: June 12, 2006
Reply to Office Action of March 10, 2006

AMENDMENTS TO THE SPECIFICATION:

Please amend the specification beginning on page 5, line 27 as follows:

Next, a method of depositing a HfSi_xO_y thin film on the wafer w using the foregoing thin film deposition apparatus will be described. It will be noted that use of the terms "M times" and "N times" throughout the specification means a first plurality of (M) times and a second plurality of (N) times, respectively, where M and N are each whole numbers that may be different or the same number as each other.